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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of:

WILLIAM R. LIVESAY, ET AL.

Docket: EV-1

Serial Number: 10/090,465

Group Art Unit:

Filed: March 4, 2002

Examiner:

For: METHOD AND APPARATUS FOR MODIFICATION OF CHEMICALLY AMPLIFIED
PHOTORESIST BY ELECTRON BEAM EXPOSURE

DISCLOSURE UNDER 37 C.F.R. 1.56

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Submitted herewith on Form PTO-1449 is a listing of documents known to Applicant in order to comply with Applicant's duty of disclosure pursuant to 37 C.F.R. 1.56. Copies of the documents are also being submitted herewith to comply with the provisions of 37 C.F.R. 1.97 and 1.98.

The submission of these documents is not intended as an admission that any or all of these materials are prior art against the claims of the present application. Applicant does not waive any rights to file Affidavits under 37 C.F.R. 1.131, to copy claims from the listed patent documents, or to take any other action which would be appropriate in the event that one or more of the documents are determined to be questionable as references against the claims of the present application.

None of these documents are believed to impair the patentability of the presently claimed invention. Nevertheless, to complete the record, formal consideration and citation of these documents is requested.

Respectfully submitted,

Richard S. Roberts
Reg. No. 27,941
P.O. Box 484
Princeton, New Jersey 08542
(609) 921-3500
Date: April 10, 2002

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE (Rev. 2-32) PATENT AND TRADEMARK OFFICE				ATTY. DOCKET NO: EV-1		SERIAL NO.:	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT				APPLICANT: WILLIAM R. LIVESAY, ET AL.			
(Use several sheets if necessary)				FILING DATE:		GROUP:	
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA	6,319,655 B1	11/20/2001	WONG, ET AL.	430	311	
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
FOREIGN PATENT DOCUMENTS							
							TRANSLATION
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	YES NO
	AI						
	AJ						
	AK						
	AL						
	AM						
	AN						
	AO						
OTHER DOCUMENTS(Including Author, Title, Date, Pertinent Pages, etc.)							
	AP	"Synthesis of Siloxanes and Silsesquioxanes for 157 nm Microlithography", Houngh V. Tran, et al. Polymeric Materials: Science & Engineering 2001, 84.xxx.					
	AQ	"Electron Beam Processing of Deep-UV Resist", M.F. Ross, et al. Pages 02-19					
	AR	"157 nm Resist Materials: Progress Report", Colin Brodsky, et al. Dept. of Chemistry and Chemical Engineering, The University of Texas at Austin, Austin, Texas 78735. Pages 3396-3401					
	AS	"E-Beam Stabilization of ArF (193nm) Photoresist for Implementation of Sub-100nm Devices", Cha-Won Koh, et al. Memory R&D Division, Hynix Semiconductor, Inc., Pages 02-11.					
	AT	"Organic Imaging Materials: A View of the Future", Michael D. Stewart, et al. Journal of Physical Organic Chemistry, J. Phys. Org. Chem. 2000; 13: 767-774					
EXAMINER				DATE CONSIDERED			
Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							